

Application No.: 10/025130

Case No.: 56008US002

REMARKS

Claims 2 – 11, 13 – 22, 25, and 28 – 33 are pending.

Rejection Under 35 U.S.C. § 102

Claims 2 – 6, 8 – 11, 13, 14, 16 – 22, 25, 29 and 33 have been rejected under 35 U.S.C. § 102(b) as being anticipated by EP 380 236 (Leir). The rejection is traversed for the following reasons.

Leir discloses water-dispersible organopolysiloxane polyurea block copolymers comprising the repeating unit of formula I (see, for example, page 3, line 30, through page 4, line 11, of Leir) that are formed by the incorporation of ionic groups along the polymer chain (see, for example, page 6, lines 53 – 54).

Applicants claim priming compositions, pressure sensitive adhesives, and articles comprising a polydiorganosiloxane polyurea copolymer comprising electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof (that is, the group consisting of electron rich tertiary amines, electron rich pyridine groups, and electron rich combinations thereof), the priming composition being capable of adhering to a substrate comprising acid functional groups.

In previous Office Actions (which are relied upon in the outstanding Office Action) the Examiner has asserted that Leir teaches electron rich groups in his organopolysiloxane polyurea block copolymers. As support for this assertion, the Examiner has referenced examples 3 and 5 and the teachings at the bottom of page 6 (see, for example, the Advisory Action dated September 24, 2004). Leir teaches block copolymers containing protonated tertiary amine (that is ionic or ionized tertiary amine) containing segments (see, for example, page 9, lines 24 – 25, teaching protonation of tertiary amine containing segments, and page 6, lines 54 – 58, teaching ionization of amine groups). Leir does not, however, appear to teach or suggest electron rich tertiary amines, electron rich pyridine groups, or electron rich combinations thereof. Leir teaches protonating the amine groups with a strong acid to generate ionic groups in order to make his block copolymers water-dispersible.

In addition, Leir does not teach or suggest that electron rich groups would provide self-priming capability. Leir therefore does not teach or suggest the claimed invention. Applicants respectfully request that the rejection under §102 based on Leir be withdrawn.

Application No.: 10/025130Case No.: 56008US002**Rejection Under 35 U.S.C. § 103**

Claims 7, 15, and 28 have been rejected under 35 U.S.C. § 103 as being unpatentable over Leir.

As discussed above, Leir does not teach or suggest electron rich groups selected from the group consisting of tertiary amine groups, pyridine groups, and combinations thereof. Leir does not teach or suggest that electron rich groups would provide self-priming capability or that electron rich groups would enable adherence to substrates comprising acid functional groups (that is, substrates comprising groups such as, for example, carboxylic acid, phosphoric acid, or sulfuric acid) such as, for example, poly(ethylene/acrylic acid), poly(ethylene/methacrylic acid), or poly(ethylene/vinyl acetate) substrates. Applicants have discovered that the compositions of the invention exhibit surprising shear strength relative to conventional silicone polyurea pressure sensitive adhesive when coated onto substrates comprising acid functional groups (see, for example, page 30 wherein the shear strength of coatings comprising the composition of the invention were 10,000 mins.)

Applicants therefore respectfully request that the rejection under § 103 based upon Leir be withdrawn.

Concluding Remarks

In view of the above, it is submitted that the application is in condition for allowance. Reconsideration and allowance of Applicants' claims are respectfully requested.

Respectfully submitted,

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Date

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